

13/D (1) Amendt D 4/25/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:

NAKAMURA et al.

Serial No.:

09/708,450

Filed:

November 9, 2000

For:

A SEMICONDUCTOR INTEGRATED CIRCUIT DEVICE

AND THE METHOD THEREOF

Group:

2811

Examiner:

D. Owens

AMENDMENT AFTER FINAL REJECTION

BOX AF

Commissioner for Patents Washington, D.C. 20231

April 21, 2003

Sir:

In response to the Office Action dated November 20, 2002, please amend the above-identified application as follows.

IN THE CLAIMS:

Please cancel claims 23 and 27 without prejudice or disclaimer.

Please amend claims 20-22, 24-26 and 28-34 as follows:

- 20. (Twice Amended) A method of producing a semiconductor integrated circuit device comprising the steps of:
- (a) forming bit lines and a first layer wiring over MISFET on a main plane of a semiconductor substrate through a first inter-layer insulating film, forming a second inter-layer insulating film and an electrode-forming insulating film, and etching holes in said electrode-forming insulating film;

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